

L Number	Hits	Search Text	DB	Time stamp
2	551236	resist or photoresist or photo-resist or photosensitive or photo-sensitive or (senstive near (photo or light or radiation or energy))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2001/11/30 16:40
3	231522	carbon adj dioxide or co2 or "co.sub.2"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2001/11/30 15:51
4	1499642	polymer or polymeric or fluoropolymer or monomer	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2001/11/30 15:52
1	182	KENDALL-JONATHAN-L-.in. DESIMONE-JOSEPH-M-.in. DESIMONE-J-M-.in. DESIMONE-JOSEPH-.in. CARBONELL-RUBEN-G-.in. CARBONELL-R-.in. CARBONELL-R-G-.in. DESIMONE-J-M-.in.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2001/11/30 15:54
5	13	(KENDALL-JONATHAN-L-.in. DESIMONE-JOSEPH-M-.in. DESIMONE-J-M-.in. DESIMONE-JOSEPH-.in. CARBONELL-RUBEN-G-.in. CARBONELL-R-.in. CARBONELL-R-G-.in. DESIMONE-J-M-.in.) and (resist or photoresist or photo-resist or photosensitive or photo-sensitive or (senstive near (photo or light or radiation or energy))) and (carbon adj dioxide or co2 or "co.sub.2") and (polymer or polymeric or fluoropolymer or monomer)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2001/11/30 16:59
6	42	(resist or photoresist or photo-resist or photosensitive or photo-sensitive or (senstive near (photo or light or radiation or energy))) with (carbon adj dioxide or co2 or "co.sub.2") with (polymer or polymeric or fluoropolymer or monomer)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2001/11/30 16:42
8	166	((resist or photoresist or photo-resist or photosensitive or photo-sensitive or (senstive near (photo or light or radiation or energy))) same (carbon adj dioxide or co2 or "co.sub.2") same (polymer or polymeric or fluoropolymer or monomer)) not (((resist or photoresist or photo-resist or photosensitive or photo-sensitive or (senstive near (photo or light or radiation or energy))) with (carbon adj dioxide or co2 or "co.sub.2") with (polymer or polymeric or fluoropolymer or monomer)) or ((KENDALL-JONATHAN-L-.in. DESIMONE-JOSEPH-M-.in. DESIMONE-J-M-.in. DESIMONE-JOSEPH-.in. CARBONELL-RUBEN-G-.in. CARBONELL-R-.in. CARBONELL-R-G-.in. DESIMONE-J-M-.in.) and (resist or photoresist or photo-resist or photosensitive or photo-sensitive or (senstive near (photo or light or radiation or energy))) and (carbon adj dioxide or co2 or "co.sub.2") and (polymer or polymeric or fluoropolymer or monomer))))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2001/11/30 16:14
9	247	(resist or photoresist or photo-resist or photosensitive or photo-sensitive or (senstive near (photo or light or radiation or energy))) with (plasma with polymeriz\$5 or ppms!)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2001/11/30 16:43

10	1	((resist or photoresist or photo-resist or photosensitive or photo-sensitive or (sensitive near (photo or light or radiation or energy))) with (plasma with polymeriz\$5 or ppms!)) same (carbon adj dioxide or co2 or "co.sub.2")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2001/11/30 16:33
11	107	(photosensitive or photo-sensitive or (sensitive near (photo or radiation or light or energy))) with (plasma with polymeriz\$5 or ppms!)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2001/11/30 16:35
12	16	((photosensitive or photo-sensitive or (sensitive near (photo or radiation or light or energy))) with (plasma with polymeriz\$5 or ppms!)) and (carbon adj dioxide or co2 or "co.sub.2")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2001/11/30 16:35
13	609228	resist or photoresist or photo-resist or photosensitive or photo-sensitive or (sensitive near (photo or light or radiation or energy))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2001/11/30 16:41
15	5	((resist or photoresist or photo-resist or photosensitive or photo-sensitive or (sensitive near (photo or light or radiation or energy))) with (carbon adj dioxide or co2 or "co.sub.2") with (polymer or polymeric or fluoropolymer or monomer)) not ((resist or photoresist or photo-resist or photosensitive or photo-sensitive or (sensitive near (photo or light or radiation or energy))) with (carbon adj dioxide or co2 or "co.sub.2") with (polymer or polymeric or fluoropolymer or monomer))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2001/11/30 16:42
16	253	(resist or photoresist or photo-resist or photosensitive or photo-sensitive or (sensitive near (photo or light or radiation or energy))) with (plasma with polymeriz\$5 or ppms!)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2001/11/30 16:44
18	0	((photosensitive or photo-sensitive or (sensitive near (photo or radiation or light or energy))) with (plasma with polymeriz\$5 or ppms!)) with develop\$4 with (carbon adj dioxide or co2 or "co.sub.2")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2001/11/30 16:44
19	719	((carbon adj dioxide or co2 or "co.sub.2") with (polymer or polymeric or fluoropolymer or monomer)) same (light or radiation or energy or expos\$3 or irradiat\$5)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2001/11/30 16:47
21	365	((carbon adj dioxide or co2 or "co.sub.2") with (polymer or polymeric or fluoropolymer or monomer)) with (light or radiation or energy or expos\$3 or irradiat\$5)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2001/11/30 16:48
20	31	((carbon adj dioxide or co2 or "co.sub.2") with (polymer or polymeric or fluoropolymer or monomer)) same (light or radiation or energy or expos\$3 or irradiat\$5) same (imagewise or patternwise or mask or photo-mask or pattern\$3 or photomask or reticle)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2001/11/30 17:00
22	485	(carbon adj dioxide or co2 or "co.sub.2") with (polymer or polymeric or fluoropolymer or monomer) with (coat\$3 or deposit\$5 or form\$3 or appl\$4) with (layer or film or coating)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2001/11/30 16:55
24	27	(carbon adj dioxide or co2 or "co.sub.2") near3 (polymer or polymeric or fluoropolymer or monomer) near3 (coat\$3 or deposit\$5 or form\$3 or appl\$4) near3 (layer or film or coating)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2001/11/30 17:02

25	2	((carbon adj dioxide or co2 or "co.sub.2") near3 (polymer or polymeric or fluoropolymer or monomer) near3 (coat\$3 or deposit\$5 or form\$3 or appl\$4) near3 (layer or film or coating)) and (resist or photoresist or photo-resist or photosensitive or photo-sensitive or (sensitive near (photo or light or radiation or energy)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2001/11/30 16:59
26	4	((carbon adj dioxide or co2 or "co.sub.2") near3 (polymer or polymeric or fluoropolymer or monomer) near3 (coat\$3 or deposit\$5 or form\$3 or appl\$4) near3 (layer or film or coating)) and ((light or radiation or energy or expos\$3 or irradiat\$5) same (imagewise or patternwise or mask or photo-mask or pattern\$3 or photomask or reticle))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2001/11/30 17:01
27	5	((("6001418") or ("6083565") or ("5739223") or ("5665527") or ("6045877")).PN.	USPAT; US-PGPUB	2001/11/30 17:02
28	5	((("6001418") or ("6083565") or ("5739223") or ("5665527") or ("6045877")).PN.) and ((resist or photoresist or photo-resist or photosensitive or photo-sensitive or (sensitive near (photo or light or radiation or energy))) or (carbon adj dioxide or co2 or "co.sub.2") or (polymer or polymeric or fluoropolymer or monomer))	USPAT; US-PGPUB	2001/11/30 17:08
30	4	((("6001418") or ("6083565") or ("5739223") or ("5665527") or ("6045877")).PN.) and ((resist or photoresist or photo-resist or photosensitive or photo-sensitive or (sensitive near (photo or light or radiation or energy))) and (carbon adj dioxide or co2 or "co.sub.2") and (polymer or polymeric or fluoropolymer or monomer))	USPAT; US-PGPUB	2001/11/30 17:04